

## Electrospinning preparation of large surface area, hierarchically porous, and interconnected carbon nanofibrous network using polysulfone as a sacrificial polymer for high performance supercapacitor

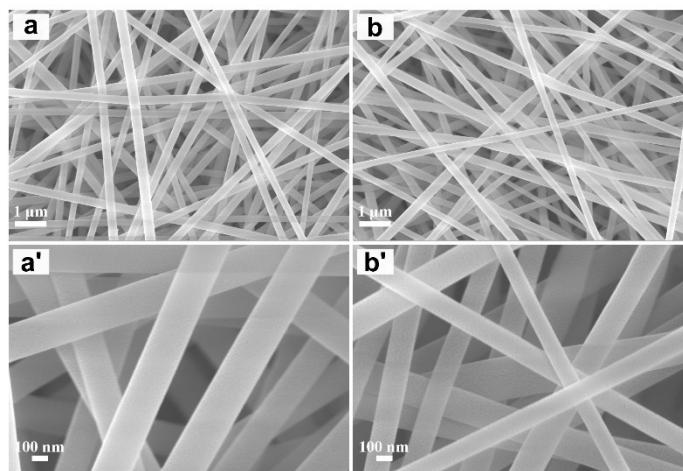
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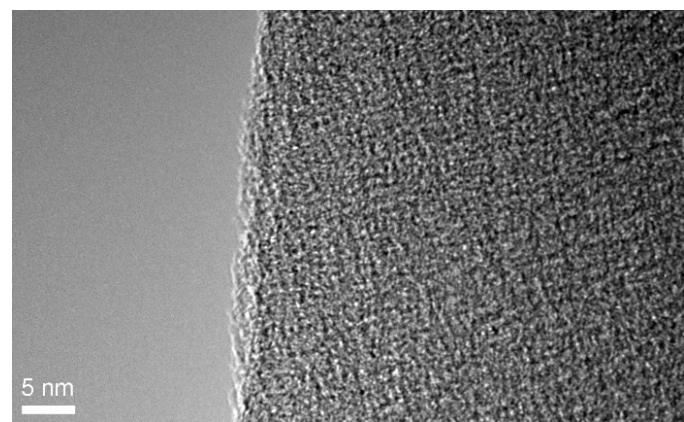
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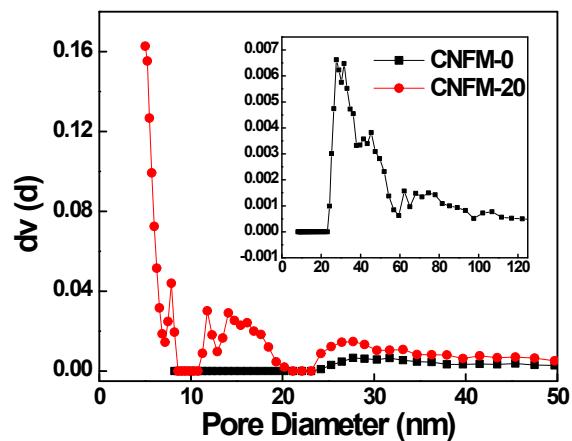
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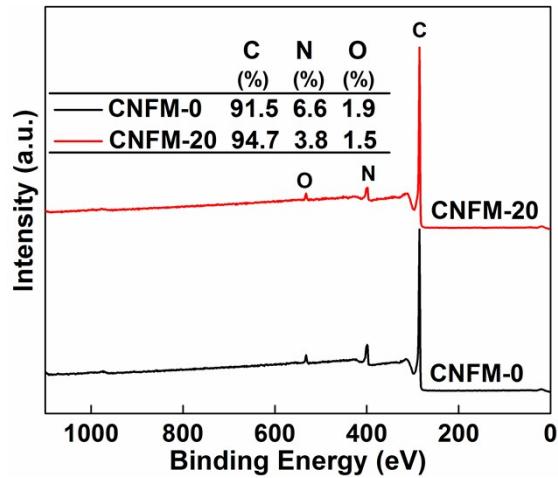
**Figure S1.** SEM images of electrospun PAN nanofibrous mat (a, a') and electrospun PSF/PAN nanofibrous mat (b, b')



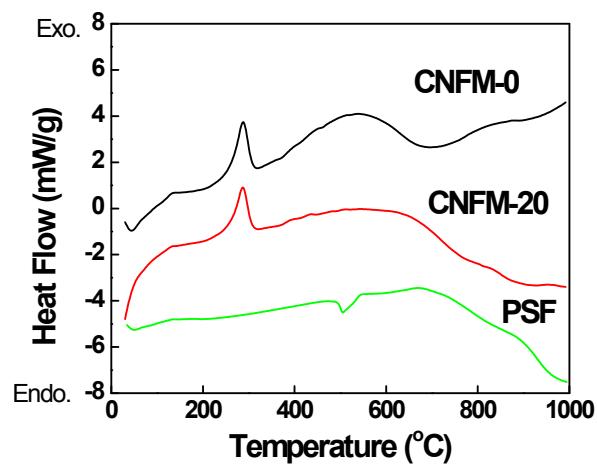
**Figure S2.** HRTEM image of CNFM-20.



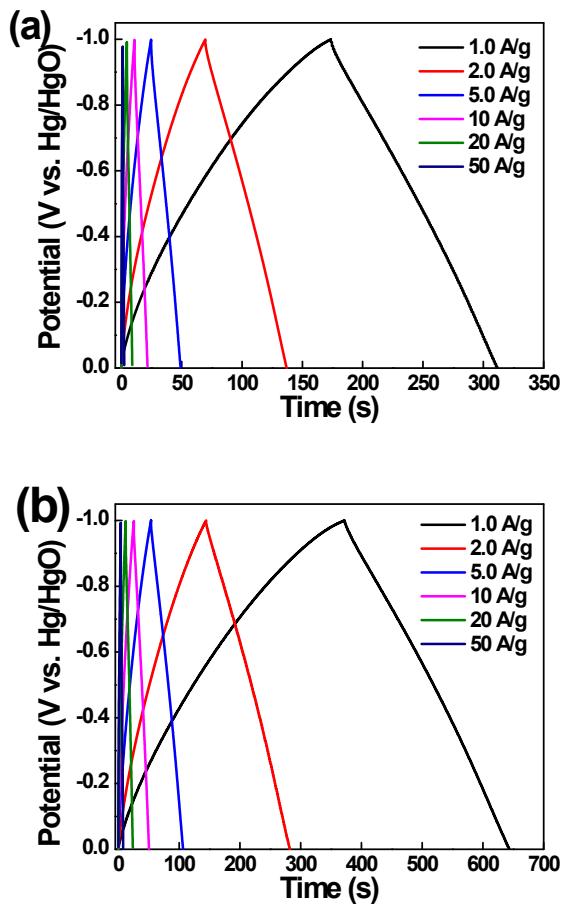
**Figure S3.** Pore size distribution of CNFM-0 and CNFM-20.



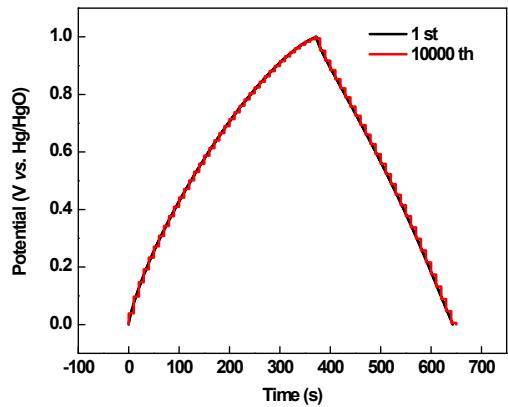
**Figure S4.** XPS spectra of CNFM-0 and CNFM-20.



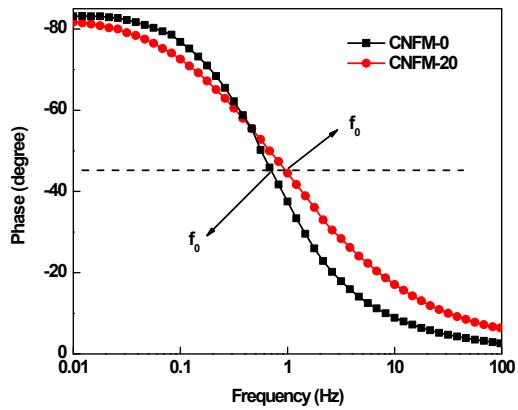
**Figure S5.** DSC curves of PSF, CNFM-0 and CNFM-20.



**Figure S6.** GCD curves of CNFM-0 (a) and CNFM-20 (b) at current densities from 1.0 A/g to 50 A/g in a three-electrode configuration and 2.0 M KOH electrolyte.



**Figure S7.** GCD curves of the CNFM-20 based electrode under the current density of 1.0 A/g at the 1<sup>st</sup> and the 10000<sup>th</sup> cycle.



**Figure S8.** The Bode plots for the CNFM-0 and CNFM-20 electrodes.

**Table S1:** Performance of supercapacitors based on electrospun carbon nanofibrous materials

Carbon source	Pore-forming agent	Carbonization temperature (°C)	Connected carbon fiber network	S <sub>BET</sub> (m <sup>2</sup> /g)	V <sub>tot</sub> (cm <sup>3</sup> /g)	Capacitance (F/g)	Cycling numbers	Retention rate	Ref.
PAN	PSF	800	Yes	763	0.51	272 (1.0 A/g)	5000	100	Our work
PAN	PVP/CO <sub>2</sub>	970	Yes	531	-	221	-	-	1
PAN	PMMA	800	No	224	0.25	210 (2 mV/s)	2000	100	2
PAN	Steam	700	No	1230	0.55	173 (10 mA/g)	-	-	3
PAN	Zinc acetate	800	No	1404	0.327	178.2 (1 mA/cm <sup>2</sup> )	1000	75	4
PAN	ZnCl <sub>2</sub>	800	No	550	0.34	130 (2 mV/s)	-	-	5
PAN	CaCO <sub>3</sub>	800	No	679	0.41	251 (0.5 A/g)	5000	88	6
PAN	CA	800	No	1160	0.807	245 (1 mA/cm <sup>2</sup> )	1000	96	7
PAN	Phenylsilane	800	No	800	-	180 (20 mA/cm <sup>2</sup> )	-	-	8
PAN	H <sub>3</sub> PO <sub>4</sub>	800	No	709	0.356	156 (0.5 A/g)	1000	96.5	9
Resole phenolic	KOH	800	No	597	0.27	256 (0.2 A/g)	1000	92	10
Novolac phenolic	KOH	750	No	1520	0.71	202 (1 mA/cm <sup>2</sup> )	10000	92	11
cellulose	CO <sub>2</sub>	1000	Yes	520	0.3	241.4 (1.0 A/g)	10000	99.9	12
PBI	Steam	800	No	1220	0.2	178 (5 mA/g)	-	-	13
PAA	Steam	750	No	1453	0.563	175 (1000 mA/g)	-	-	14

## Reference

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